

Material Characterization

● CMP (Chemical Mechanical Planarization)

Particle Size

Laser Diffraction/Scattered particle size dust

Partica LA-960V2

- Wide range
- High-precision Warranty
- High concentration measurement available



Particle size

Analysis and Measurement Technology

- ▶ Laser diffraction/scattering
- ▶ Dynamic light scattering
- ▶ Doppler effect
- ▶ Centrifugation
- ▶ Absorbency
- ▶ Electro chemistry
- ▶ Flow control

Chemical Concentration Monitor

Non-contact chemical concentration monitor

CS-900

- Eliminates contamination
- Easy installation
- Compact



Concentration

Centrifugal Nanoparticle Analyzer

Partica CENTRIFUGE

- Can be measured from stock solution to dilute samples
- Observation of small amounts of foreign substances
- Long-term stability measurement

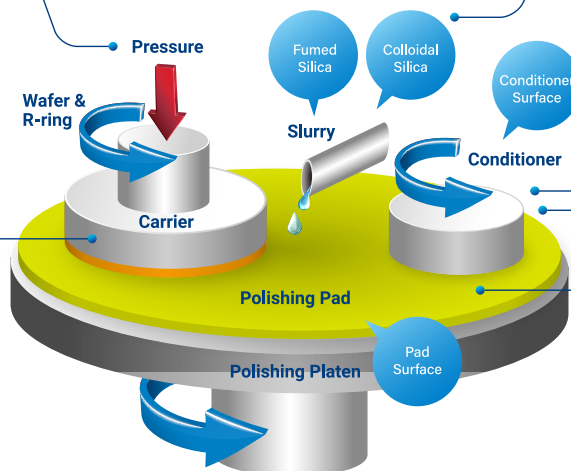
Zeta potential

Zeta Potential

Nanoparticle analyzing device

nanoPartica SZ-100V2

- Particle size, zeta potential, and molecular weight measurement
- Compatible with 0.3nm particle size
- Measurable from diluted samples to high concentration samples



IPA Concentration

In line gas concentration monitor

IR-300

- Real time monitoring
- Multiple calibration curve function
- Monitor concentration pressure and temperature



IPA in solutions

pH Measurement

Trace sampling pH monitor

UP-100 Series

- Small amount sampling
- Real time measurement
- Significant reduction in maintenance cycles



Monitor PH value

Film Quality

Spectroscopic ellipsometer

UVISEL Plus

- Evaluation of uniformity and film quality
- Analyze film thickness, refractive index, and extinction coefficient of ultra thin films



Quality assesment